

## IMAGE SENSOR AND METHOD FOR FABRICATING THE SAME

### ABSTRACT

5           An image sensor includes a substrate in which photoelectric elements have been  
formed, and an array of optical path conversion elements formed at a light so that the optical  
path converted light may be incident on the substrate, wherein each of the optical path  
conversion elements has different tangent line gradients on the corresponding parts of  
incident surfaces according to distances from the center of the image sensor in order to  
10   compensate for differences of incident angles of incident light according to the distances  
from the center of the image sensor. In addition, a method for fabricating the image sensor  
fabricates the optical path conversion elements according to a photolithography process using  
a gray scale mask, combinations of the photolithography process and a reactive ion etching  
process, or combinations of the photolithography process, the reactive ion etching process,  
15   and an UV-molding process.